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December 9, 2008

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Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

> Re: U.S. Patent No. 6,955,720

Issued: October 18, 2005

Plasma Deposition of Spin Chucks to Reduce Contamination of Silicon Wafers

Patentees: GURER et al. Our Ref: 1857.6780001

Sir

Transmitted herewith for appropriate action are the following documents:

- 1. Power of Attorney to Prosecute Applications Before the USPTO; and
- Statement Under 37 C.F.R. 3.73(b).

The above-listed documents are filed electronically through EFS-Web.

The U.S. Patent and Trademark Office is hereby authorized to charge any fee deficiency, or credit any overpayment, to our Deposit Account No. 19-0036.

Respectfully submitted,

STERNE, KESSLER, GOLDSTEIN & FOX P.L.L.C.

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GJP/awt Enclosures

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